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APPLICATION NO.	FI	LING DATE	FIRST NAMED INVENTOR		ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/982,654 10/18/2001		10/18/2001	Brian K. Kirkpatrick		TI-31459	8114
23494	7590	04/23/2003				
TEXAS INSTRUMENTS INCORPORATED					EXAMINER	
P O BOX 655474, M/S 3999 DALLAS, TX 75265					KEBEDE, BROOK	
				•	ART UNIT	PAPER NUMBER
				•	2823	2
					DATE MAILED: 04/23/2003	3

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	7					
	09/982,654	KIRKPATRICK ET AL.	KIRKPATRICK ET AL.					
Office Action Summary	Examiner	Art Unit						
	Brook Kebede	2823						
The MAILING DATE of this communication a Period for Reply	ppears on the cover shee	et with the correspondence address						
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION  - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, ar  - If NO period for reply is specified above, the maximum statutory perion for reply within the set or extended period for reply will, by stated that the period for reply within the set or extended period for reply will, by stated that the material patent term adjustment. See 37 CFR 1.704(b).  Status	N. 1.136(a). In no event, however, m reply within the statutory minimum of will apply and will expire SIX (6)	ay a reply be timely filed  of thirty (30) days will be considered timely.  MONTHS from the mailing date of this communication.  ne ABANDONED (35 U.S.C. § 133).						
1) Responsive to communication(s) filed on 1	8 October 2001 .							
·	This action is non-final.							
Since this application is in condition for allo	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
closed in accordance with the practice und  Disposition of Claims	er <i>Ex parte Quayle</i> , 193	5 C.D. 11, 453 O.G. 213.						
•	4)⊠ Claim(s) <u>1-19</u> is/are pending in the application.							
4a) Of the above claim(s) is/are without	Irawn from consideration	i.						
5)⊠ Claim(s) <u>12-19</u> is/are allowed.	5)⊠ Claim(s) <u>12-19</u> is/are allowed.							
6)⊠ Claim(s) <u>1,2,4,6 and 9-11</u> is/are rejected.								
7)⊠ Claim(s) <u>3,5,7 and 8</u> is/are objected to.								
8) Claim(s) are subject to restriction and	d/or election requiremen	t.						
Application Papers	•							
9) The specification is objected to by the Exam	iner.	by the Evaminer						
10)☐ The drawing(s) filed on is/are: a)☐ ad	ccepted or b) objected to	shovence. See 37 CER 1 85(a)						
Applicant may not request that any objection to	the drawing(s) be neid in	disapproved by the Examiner.						
11) The proposed drawing correction filed on		disapproved by the Entermore						
If approved, corrected drawings are required in								
12) The oath or declaration is objected to by the	LXanimer.							
Priority under 35 U.S.C. §§ 119 and 120	aine esiasitu undor 25 l l	S C & 119(a)-(d) or (f)						
13) Acknowledgment is made of a claim for for	eign phonty under 33 O.	5.0. g 113(a)-(b) 5/ (i).						
a) All b) Some * c) None of:	anta hava haan raasiya							
<ul> <li>2. Certified copies of the priority documents have been received in Application No</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage</li> </ul>								
3. Copies of the certified copies of the papelication from the International  * See the attached detailed Office action for a	l Bureau (PCT Rule 17.2	(a)).						
14) Acknowledgment is made of a claim for dom	estic priority under 35 U	S.C. § 119(e) (to a provisional application).						
a) The translation of the foreign language	provisional application	nas been received.						
Attachment(s)								
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948 3) Information Disclosure Statement(s) (PTO-1449) Paper No	5) 🔲 No	erview Summary (PTO-413) Paper No(s) tice of Informal Patent Application (PTO-152) ter:						

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### **DETAILED ACTION**

# Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1, 2, 9, and 11 are rejected under 35 U.S.C. 102(e) as being anticipated by Cowely et al. (US/2002/0088476).

Re claim 1, Cowely et al. disclose a method for fabricating an integrated circuit, comprising the steps of forming a low-k dielectric (not labeled) layer over a semiconductor body; treating said low-k dielectric layer with a reducing plasma; treating said low-k dielectric layer with a wet solution; forming a resist pattern over said low-k dielectric layer; and etching said low-k dielectric layer using said resist pattern (see Abstract; Page 1 Paragraph 0017 and Page 2 Paragraphs 0021-0023).

Re claim 2, as applied to claim 1 above, Cowely et al. disclose wherein said reducing plasma comprises  $H_2$  and  $N_2$  (see Abstract)

Re claim 9, as applied to claim 1 above, Cowley et al. disclose all the claimed limitations including the limitation wherein said low-k dielectric layer comprises organosilicate glass (see Abstract; Page 1 Paragraph 0017 and Page 2 Paragraphs 0021-0023).

Re claim 11, as applied to claim 1 above, Cowley et al. disclose all the claimed limitations including the limitation wherein said treating step removes said resist pattern as a

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pattern re work step (see Abstract; Page 1 Paragraph 0017 and Page 2 Paragraphs 0021-0023).

## Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

4. Claims 4, 6 and 10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Cowely et al. (US/2002/0088476) in view of Geha et al. (US/5,968,851).

Re claims 4, 6 and 10, as applied to claim 1 above, Cowley et al. disclose all the claimed limitations except wherein said wet solution comprises HF comprises solvent.

Geha et al. disclose a method of treating the polished dielectric layer using HF solution comprises solvent prior formation of resist pattern in order to enhance the lateral-to-vertical wet etch ratio (see Abstract).

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Therefore, it would have been obvious to one having ordinary skill in the art at the time of applicant(s) claimed invention was made to have provided Cowley reference with treating the dielectric layer with HF wet treatment solution comprises solvent prior as taught by Geha et al. because the lateral-to-vertical wet etch ratio would have been improved.

## Allowable Subject Matter

- 5. Claims 12-19 are allowed over prior art of record.
- 6. Claims 3, 5, 7 and 8 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

#### Conclusion

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure Hsieh et al. (US/5,880,019), Chen (US/5,970,376), Lai et al. (US/6,136,680), Huang (US/6,177,364), Smith et al. (US/2002/0127840), and Aoki et al. (US/6,465,352) also disclose similar inventive subject matter.

### Correspondence

8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Brook Kebede whose telephone number is (703) 306-4511. The examiner can normally be reached on 8-5 Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on (703) 306-2794. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 308-7722 for regular communications and (703) 308-7722 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Brook Kebede

April 20, 2003

IN, DAVID COLEMAN

PRIMARY EXAMINER

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